

⁵₅₄. (amended) A method for forming a relief image on a substrate comprising:
applying on the substrate a layer of an antihalation composition comprising an
anthracene material;

B2 applying over the antihalation composition coating layer a photoresist composition.

⁶₅₅. (amended) The method of claim ⁵₅₄ wherein the antihalation composition
coating layer is crosslinked prior to applying the photoresist composition.

✓
[Please add the following new claims.

¹³₅₈. The method of claim ⁵₅₄ wherein the photoresist composition is imaged with
activating radiation and the imaged photoresist composition is treated with a developer to
provide a photoresist relief image.

¹⁴₅₉. The method of claim ¹³₅₈ wherein areas bared of photoresist upon treatment with
the developer are etched.

¹⁵₆₀. The method of claim ¹³₅₈ wherein areas bared of photoresist upon treatment with
the developer are exposed to a plasma gas.

B3 ⁵₆₁. The method of claim 58 wherein the plasma gas penetrates the antihalation
composition coating layer.

⁷₆₂. The method of claim ⁶₅₅ wherein the photoresist composition is imaged with
activating radiation and the imaged photoresist composition is treated with a developer to
provide a photoresist relief image.